



IN THE CLAIMS

RECEIVED
MAY 31 2001
TECHNOLOGY CENTER 2880

1 1. (Three Times Amended) A method of removing a particle from a surface of a
2 metal plug formed in a via comprising:
3 introducing a first agent to a metal layer;
4 polishing the metal layer with the first agent;
5 after polishing the metal layer, introducing a second agent comprising hydrogen
6 peroxide to rinse the surface of the metal plug; and
7 removing at least one particle from the surface of the metal plug.

1 9. (Three Times Amended) A method of removing at least one particle from a
2 surface of a metal plug disposed over a substrate comprising:
3 depositing a slurry onto a metal layer over the metal plug;
4 polishing the metal layer; and
5 after polishing the metal layer, rinsing the surface of the metal plug with a
6 solution comprising hydrogen peroxide.

1 18. (Three Times Amended) A method comprising:
2 polishing a metal layer over a conductive plug with a slurry;
3 after polishing the metal layer, introducing a rinsing solution onto the conductive
4 plug, the rinsing solution comprises hydrogen peroxide.